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a detector to detect information concerning displacement of the projection system;

an actuator arranged on the holder; and

a driver connected to the actuator to drive the actuator in response to detection results of the detector.

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12. (Amended) The exposure apparatus of claim 1, further comprising:

a stage that holds and moves one of the substrate and a reticle that contains the pattern, the stage being mounted to the main frame.

13. (Amended) The exposure apparatus of claim 12, wherein:

the stage includes a drive system that moves the one of the substrate and the reticle, the stage drive system including a movable part that moves with the one of the substrate and the reticle, and a stationary part that is coupled to the main frame.

14. (Amended) The exposure apparatus of claim 13, wherein the stage is a substrate stage that holds and moves the substrate.

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16. (Amended) The exposure apparatus of claim 13, wherein the stage is a reticle stage that holds and moves the reticle.

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18. (Amended) A method of making an exposure apparatus that exposes a pattern onto a substrate, the method comprising:

providing a projection system to project the pattern onto the substrate;

providing a holder connected to the projection system to hold the projection system;

providing a main frame that mounts the projection system by means of the holder;

providing a detector to detect information concerning displacement of the projection system;

providing an actuator on the holder; and

providing a driver connected to the actuator to drive the actuator in response to detection results of the detector.

27. (Amended) The method of claim 18, further comprising:

providing a main frame;

providing a stage that holds and moves one of the substrate and a reticle that contains the pattern; and

mounting the stage to the main frame.

28. (Amended) The method of claim 27, wherein the stage is a substrate stage that holds and moves the substrate.

29. (Amended) The method of claim 27, wherein the stage is a reticle stage that holds and moves the reticle.

30. (Amended) A method of exposing a pattern onto a substrate through a projection system, the method comprising:

holding the projection system with a holder;

mounting the projection system to a main frame by means of the holder;

detecting information concerning displacement of the projection system; and

driving an actuator mounted on the holder in response to the detected information.

39. (Amended) The method of claim 30, further comprising:

holding and moving one of the substrate and a reticle that contains the pattern;

and

mounting the stage to the main frame.

40. (Amended) The method of claim 39, wherein the stage is a substrate stage that holds and moves the substrate.

41. (Amended) The method of claim 39, wherein the stage is a reticle stage that holds and moves the reticle.